

REMARKS

Claims 37, 54, 55, and 75 have been amended to further describe the presently claimed invention.

The claims have been rejected as obvious in view of U.S. Patent Nos. 5,994,030, 4,868,068, and 5,178,989.

Each of these patents relate to resists, not organometallic precursors. See, '030 patent, column 2, lines 58-59; '989 patent, FIG 1, or have nothing to do with an apparatus to partially convert and then fully convert a precursor material to form a metal or metal oxide film.

The amendments to the independent claims clearly distinguishes the presently claimed invention, which relates to the conversion of organometallic precursor material without resist. The presently claimed invention is not the resist-using pattern forming and transferring process of the '989 patent, nor is it the IC wiring connecting method of the '068 patent, nor it is the resist-using method of the '030 patent. None of these patents disclose a process for preconversion and conversion of a resist-free organometallic precursor material, as presently claimed.

In view of the amendments and arguments presented above, all claims are now thought to be in condition for allowance, an indication of which is solicited. In the event that any issues remain outstanding, Applicants would appreciate the courtesy of a telephone call to the undersigned counsel to resolve such issues in an expeditious manner so as to place this application in condition for allowance.

A three month petition for extension of time and fees is concurrently filed. However, if any additional fees are determined to be due, the Commissioner is hereby authorized to charge these fees to the Morgan, Lewis & Bockius Deposit Account no. 50-0310.

Respectfully submitted,

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by


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